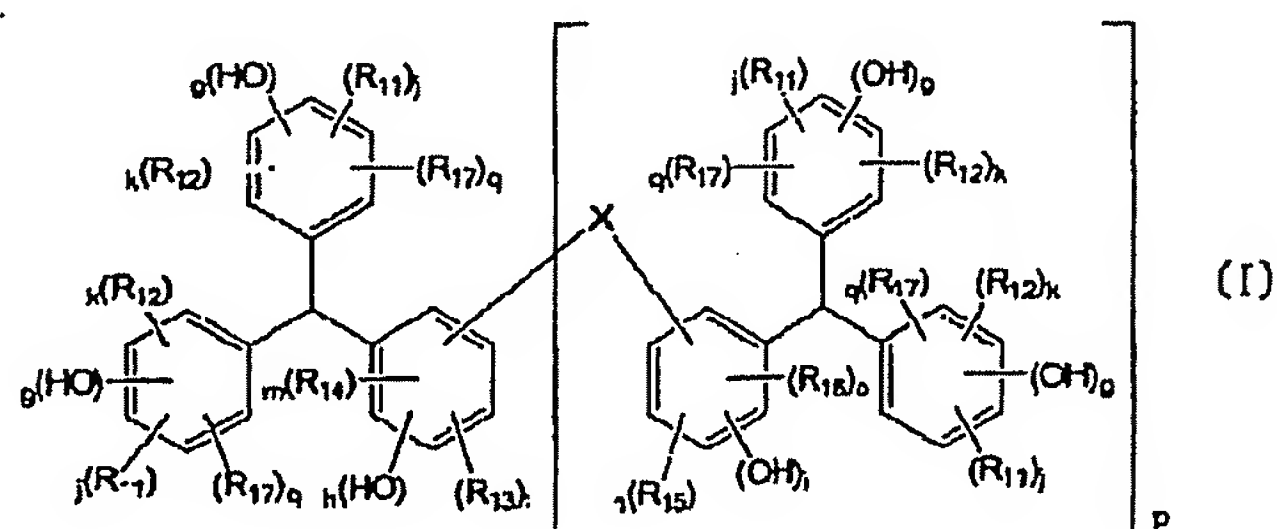


五、中文發明摘要

發明名稱：極紫外光 EUV 用光阻組成物及光阻圖型之形成方法

本發明之光阻組成物，為含有 (A1) 下述式 (I) 所示多元酚化合物 (a) 中之酚性羥基中一部份或全部被酸離性溶解抑制基所保護之保護體，與 (B) 經由曝光產生酸之酸產生劑成份之 EUV 用光阻組成物。

[化 1]

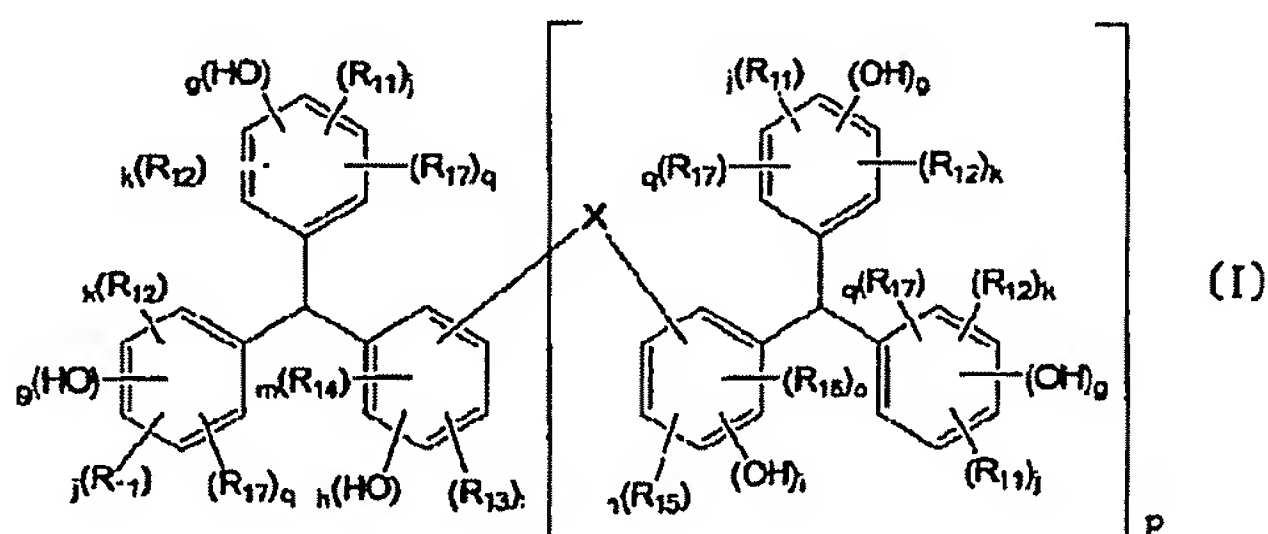


六、英文發明摘要

發明名稱：

RESIST COMPOSITION FOR EUV AND PROCESS FOR FORMING RESIST PATTERN

The resist composition of the present invention is a resist composition for the use of EUV including (A1) a protected body in which a part or all of phenolic hydroxy group in a polyphenol compound (a) represented by the following general formula (I):



is protected by an acid dissociative dissolution inhibiting agent and (B) an acid generating agent component which generates an acid by exposure.